

Rôle de la chimie de surface sur les propriétés des matériaux pour accélérateur : conditionnement et émission électronique secondaire



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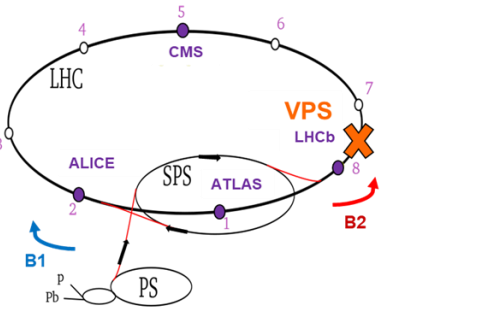
Collaboration :

V. Baglin (CERN/Technological Department, Vacuum, Surfaces & Coatings Group)

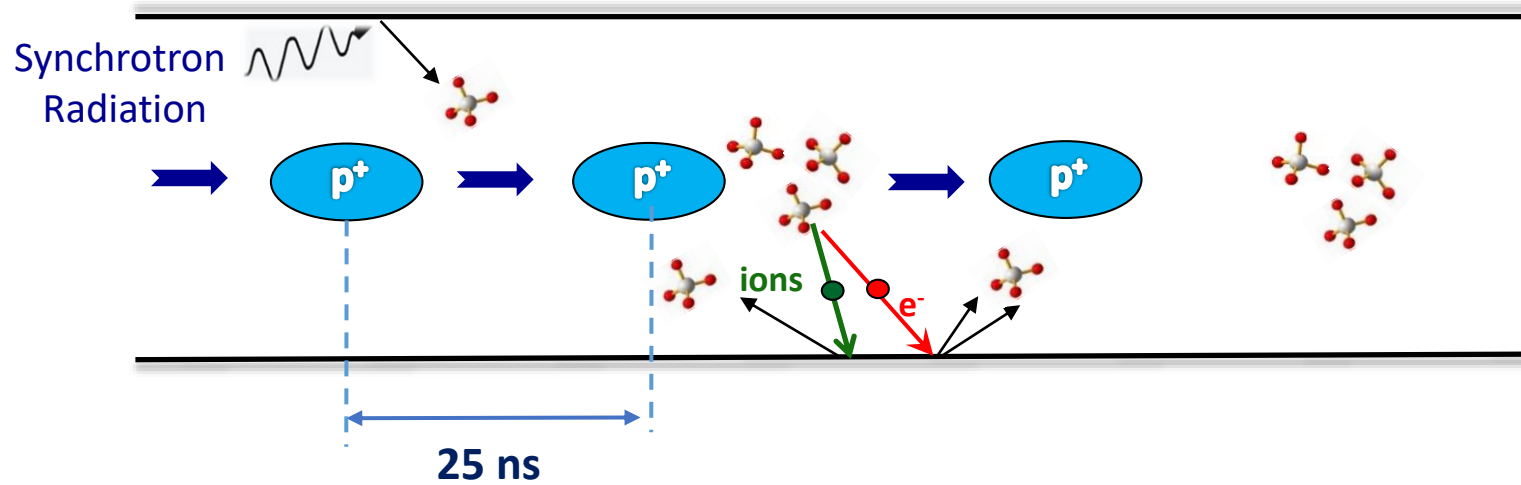
T. Proslie, Y. Kalboussi (CEA/IRFU)



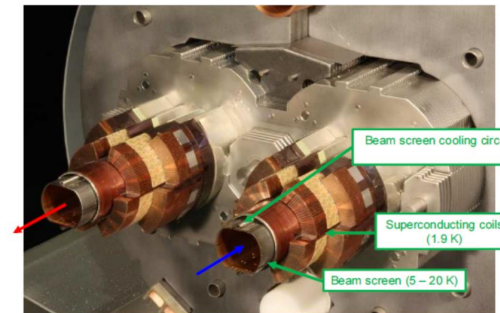
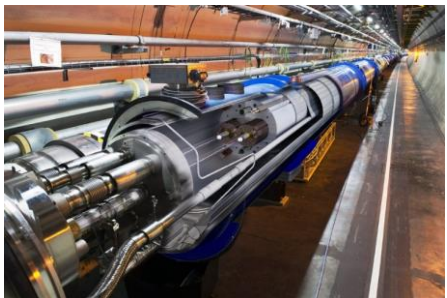
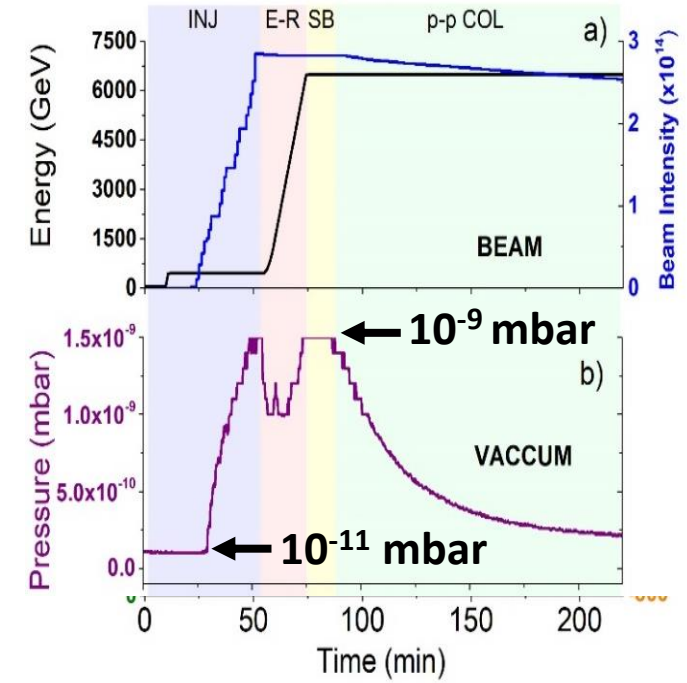
Contexte : l'exemple du LHC



Désorption Stimulée

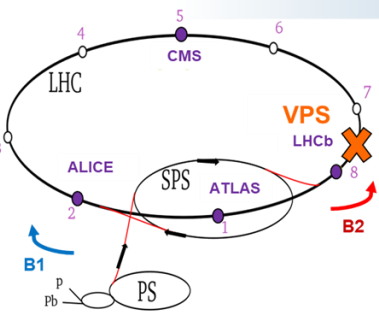


Evolution du vide dynamique dans le LHC (station 4 du VPS)

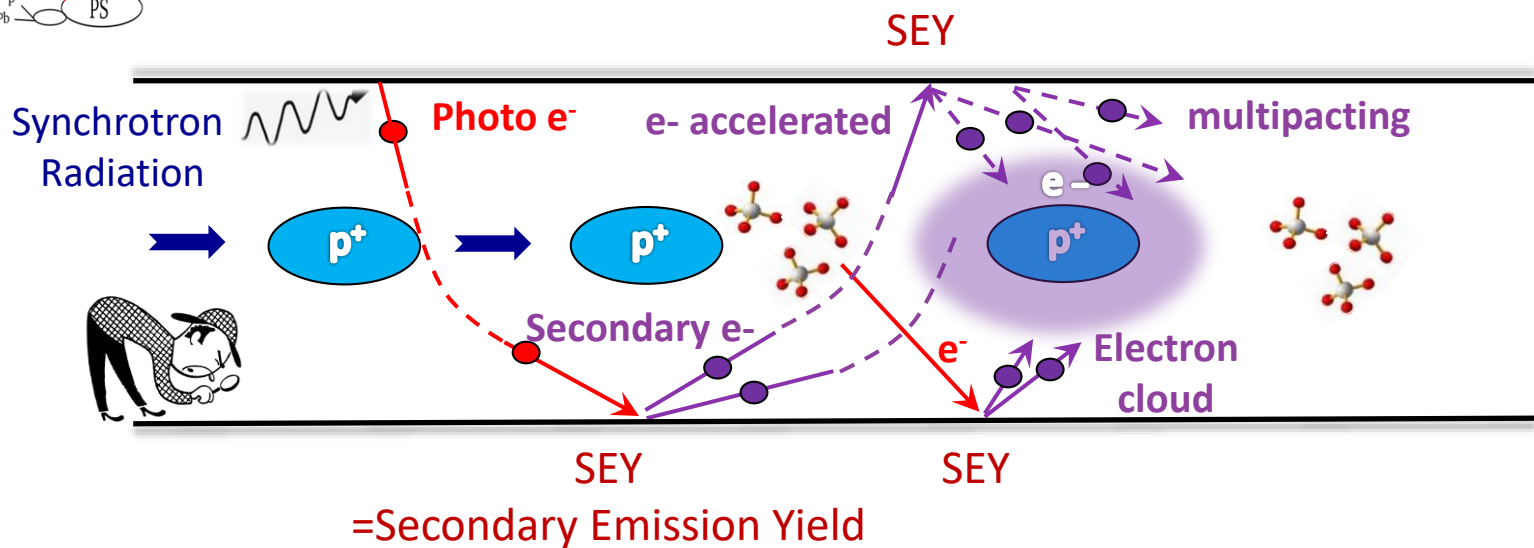




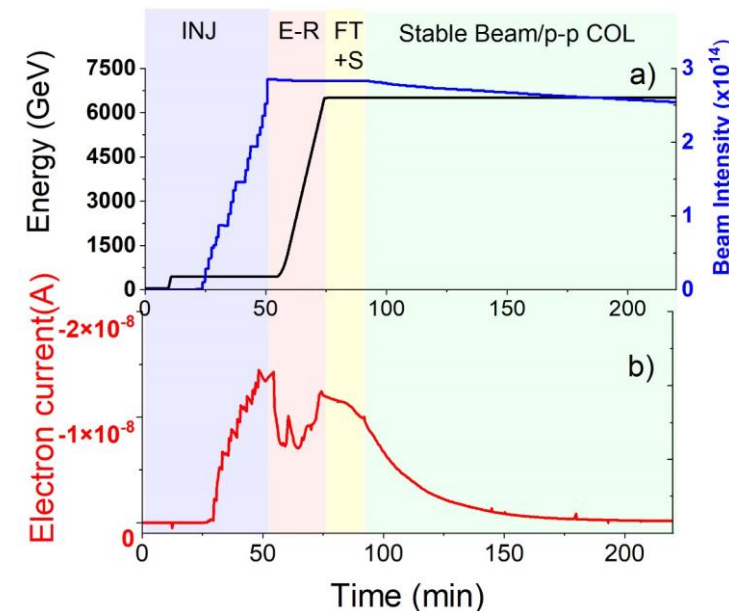
Contexte : l'exemple du LHC



Création de particules secondaires



Evolution du courant d'électrons dans le LHC (station 4 du VPS)



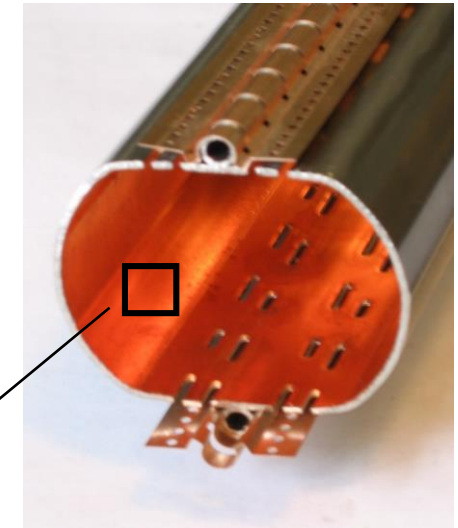
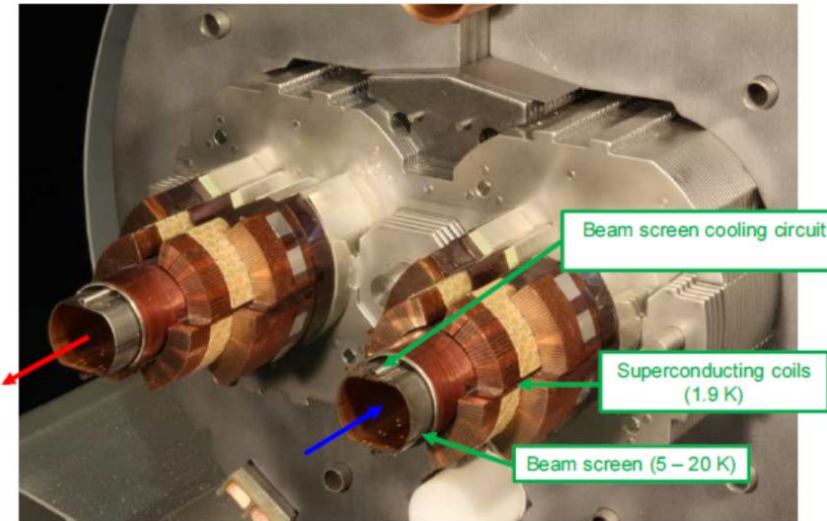
All of these phenomena may limit the performance of the LHC : **2018 LHC RUN 2** 13 TeV, 2556 b, 1.1×10^{11} ppb vs **NOMINAL PARAMETERS LHC** 14 TeV, 2808 b, 1.2×10^{11} ppb

Main objectives

- Mitigation of detrimental collective effects inside the beam lines
- Influence of the surface chemistry on these phenomena + modification of the surface chemistry under irradiation



LHC beam screen samples



Oxygen-Free Electronic copper colaminated onto stainless steel.

OFE copper = 99.99% pure copper with 0.0005% oxygen content to avoid undesirable chemical reactions with other materials



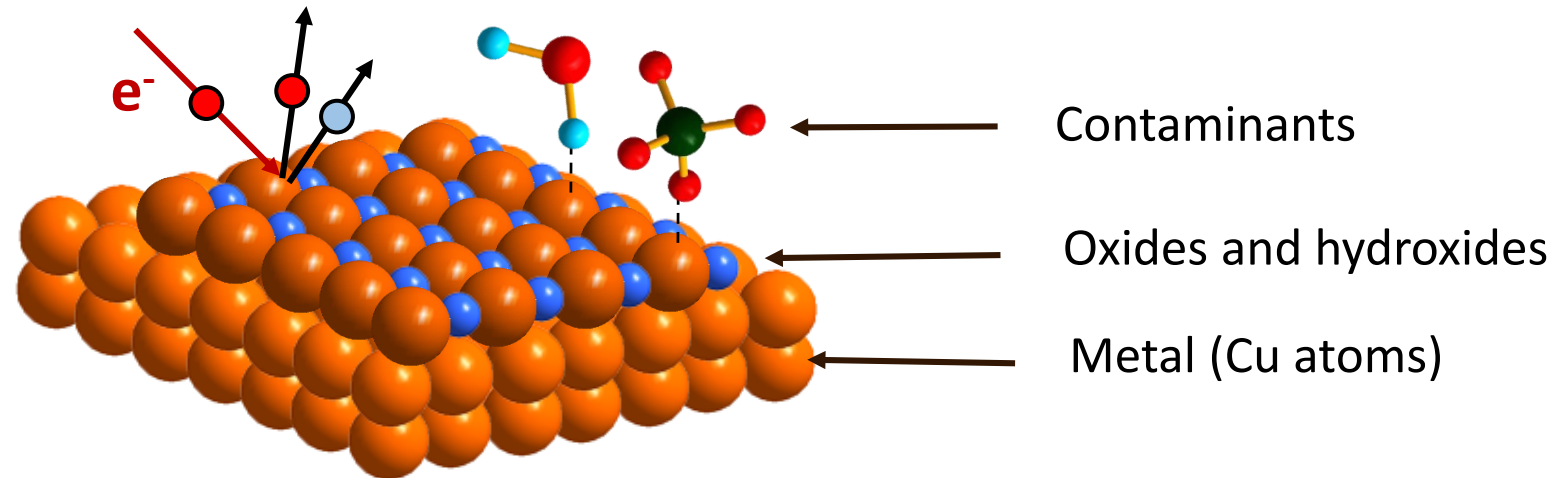
5 mm

dimensions: 5 x 5 x 2 mm thick from the CERN's stock.

- high electric conductivity
- high thermal conductivity
- low outgassing rate
- non-magnetic material



Analysis of technical surfaces



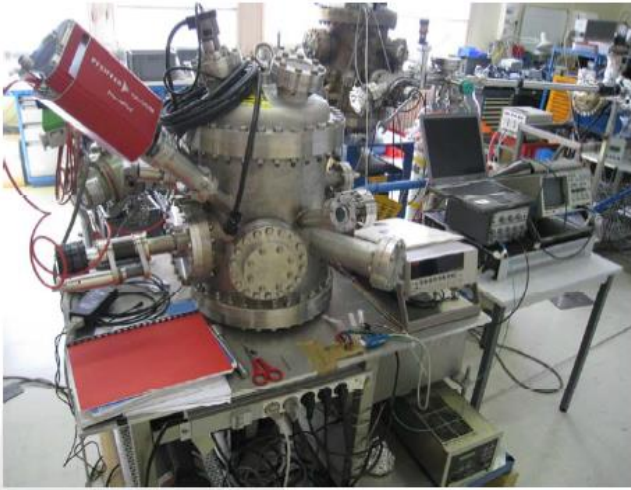
- there are **always contaminants** deposited on the surface + native oxide layers (Cu_2O et $\text{Cu}(\text{OH})_2$)
- investigated surfaces in accelerators are **technical surfaces** (and not pure Cu surfaces)

- Rôle du carbone (via les molécules hydrocarbonées initialement présentes) ?
- Rôle des oxydes/hydroxydes natifs de cuivre ?

} **Sur le SEY**

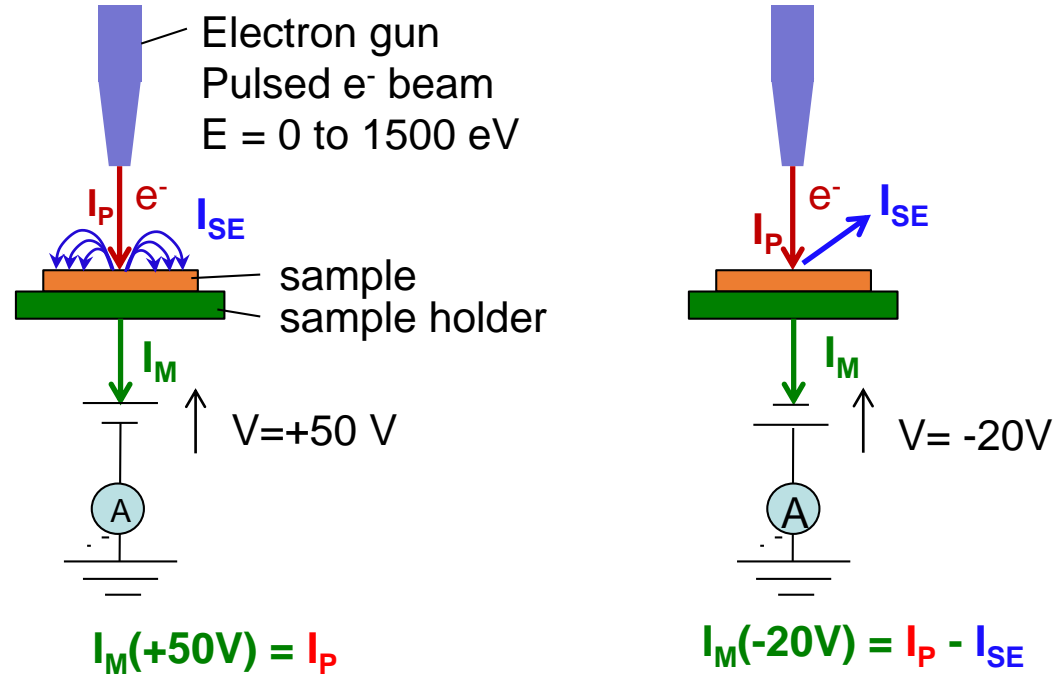


SEY measurements and conditioning in lab



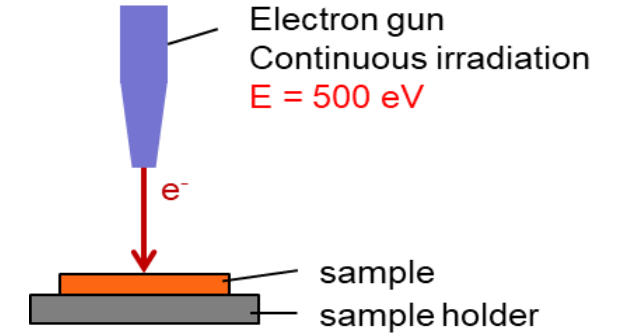
- base pressure: 5×10^{-10} mbar
- pulsed electron beam
- energy range 10 to 1500 eV
- During measurement $I = \text{qqes nA}$
- During conditioning: $I = 5 \mu\text{A}$
- SEY error (about 10%), since elastically backscattered electrons can escape
- beam spot 2.8 mm in diameter during conditioning

SEY measurements



$$SEY : \delta = 1 - \frac{I_M(-20V)}{I_M(+50V)}$$

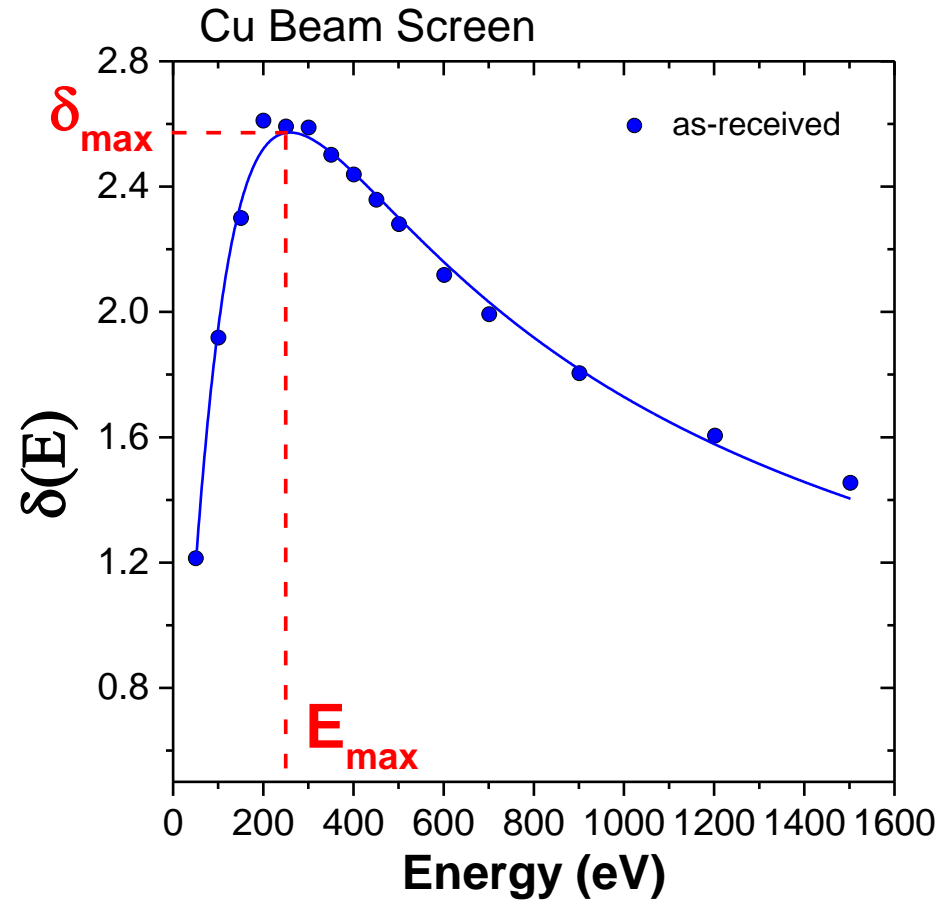
Conditioning by e^- irradiation





SEY measurements : copper beam screen

$$SEY = \frac{\text{number of SE}}{\text{incident } e^-}$$



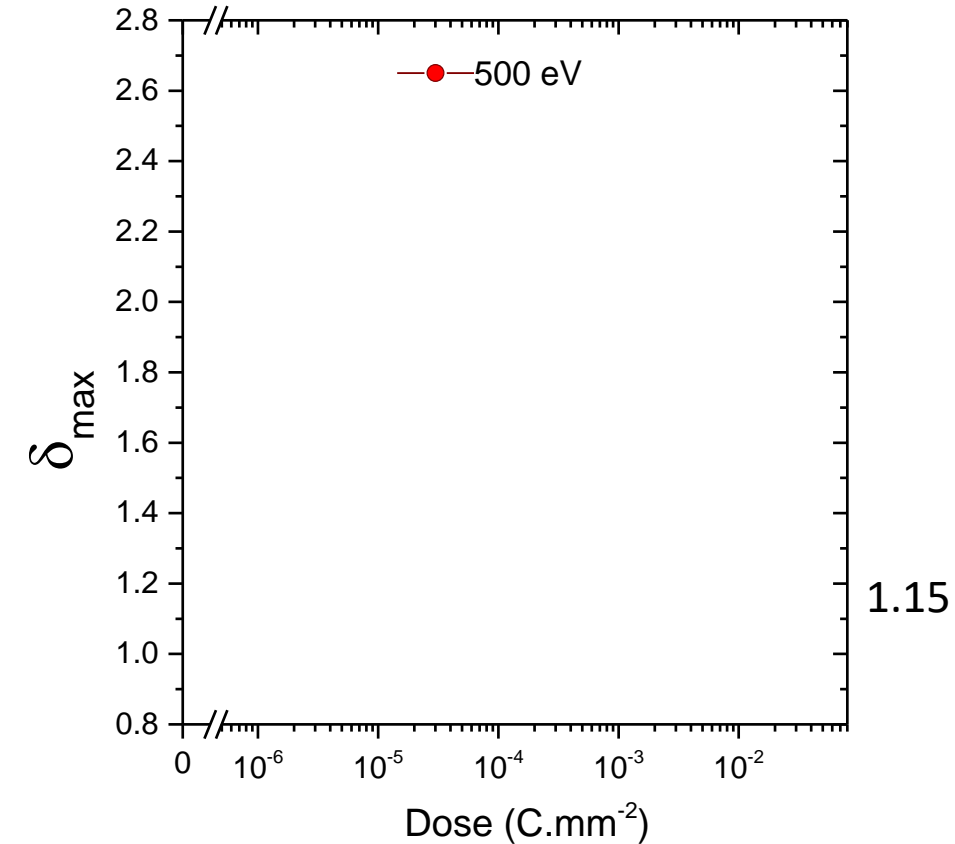
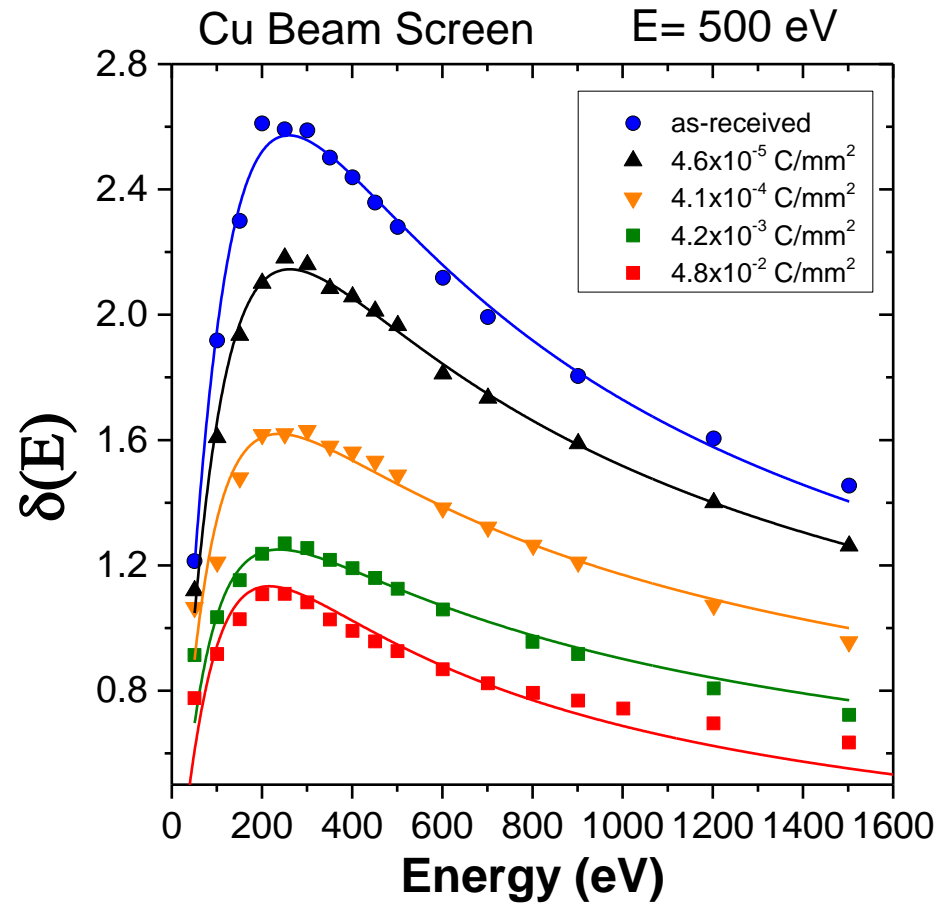
$$\delta(E) = \delta_{max} \frac{s * \left(\frac{E}{E_{max}}\right)}{s - 1 + \left(\frac{E}{E_{max}}\right)^s}$$

[Scholtz et al J of Research, 1996]

Suheyla Bilgen PhD Thesis (IJCLab 2020)



SEY measurements : copper beam screen

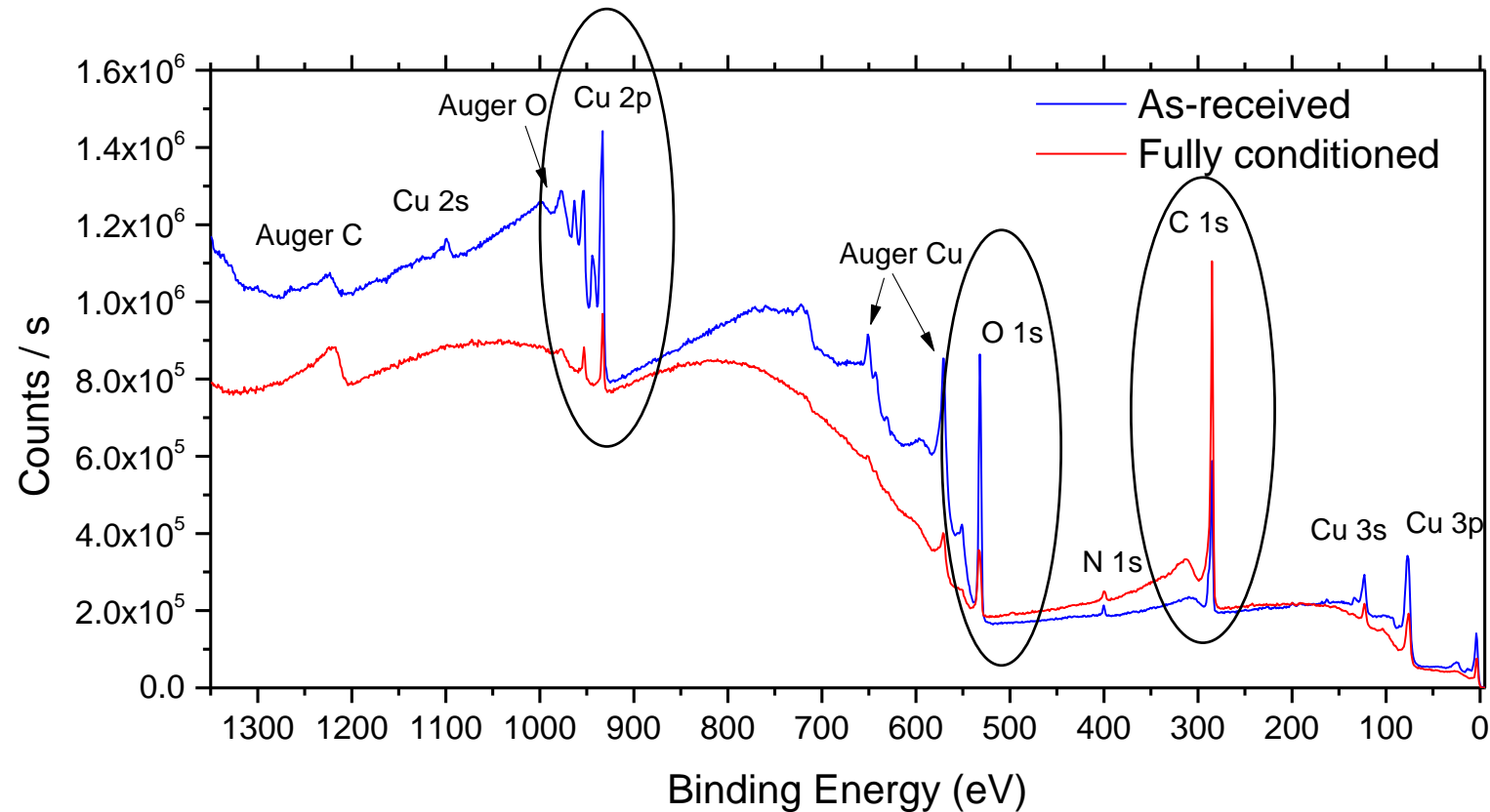


$\delta(E)$ decreases with increasing electron dose
in agreement with the literature e.g [R. Cimino et al *J. of Electron Spectr. Related Phenomena*, 2020]



XPS analysis

X-ray Photoelectron Spectroscopy

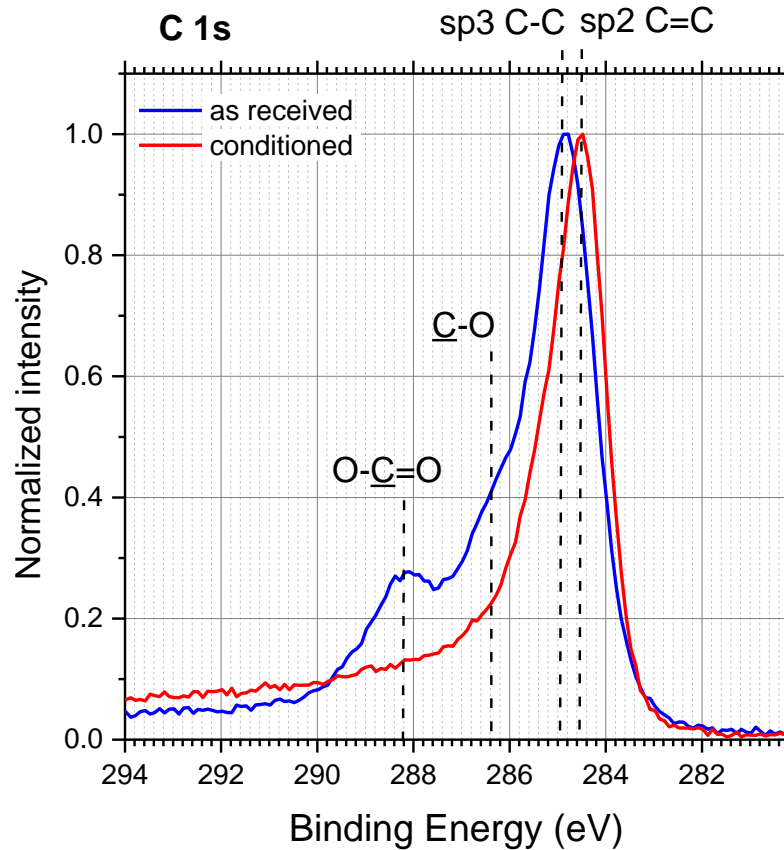


We are mainly interested in the chemical modifications of Cu, O and C induced by e- irradiation (main elements detected on the copper surface).



Carbon evolution?

XPS



Adventitious carbon (C-O, O-C=O) is removed by electron irradiation

Modification of the C hybridization induced by electron irradiation

Shift from C-C bonds (sp³) to C=C bonds (sp²)

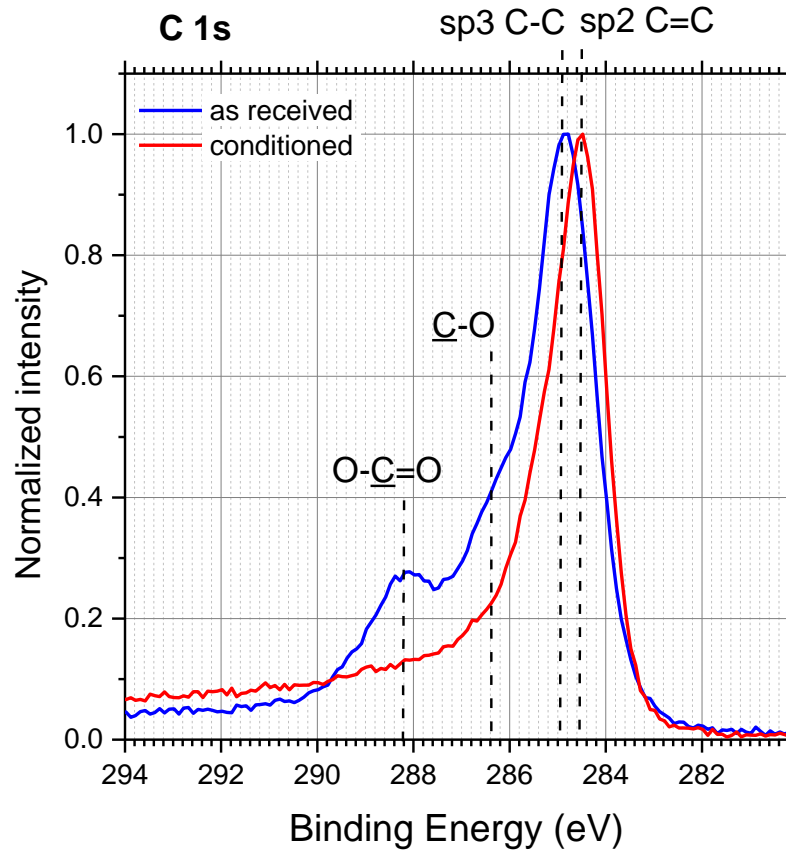
→ in agreement with the literature [R. Cimino et al, 2020]

→ For the first time, this phenomenon was investigated by TOF-SIMS (platform ANDROMEDE/IJCLab)



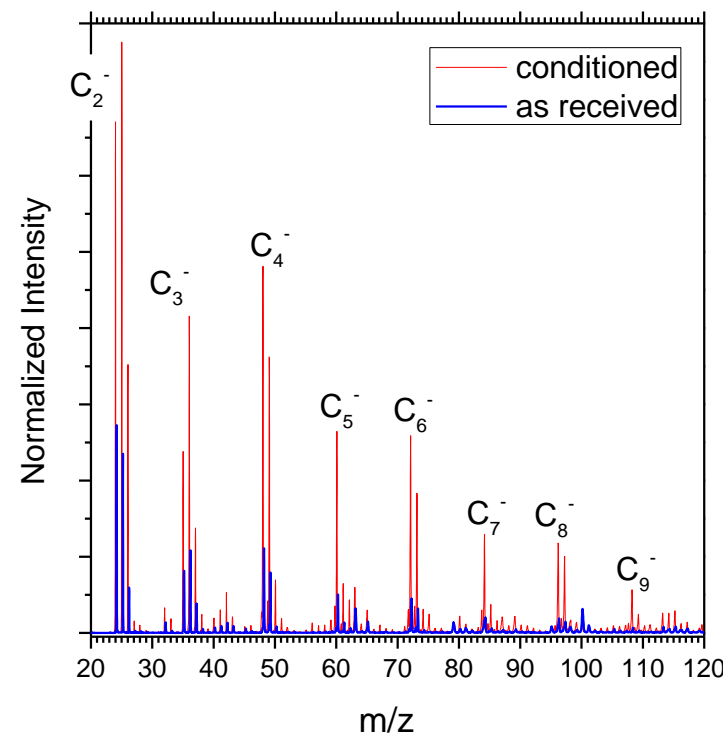
Carbon evolution?

XPS

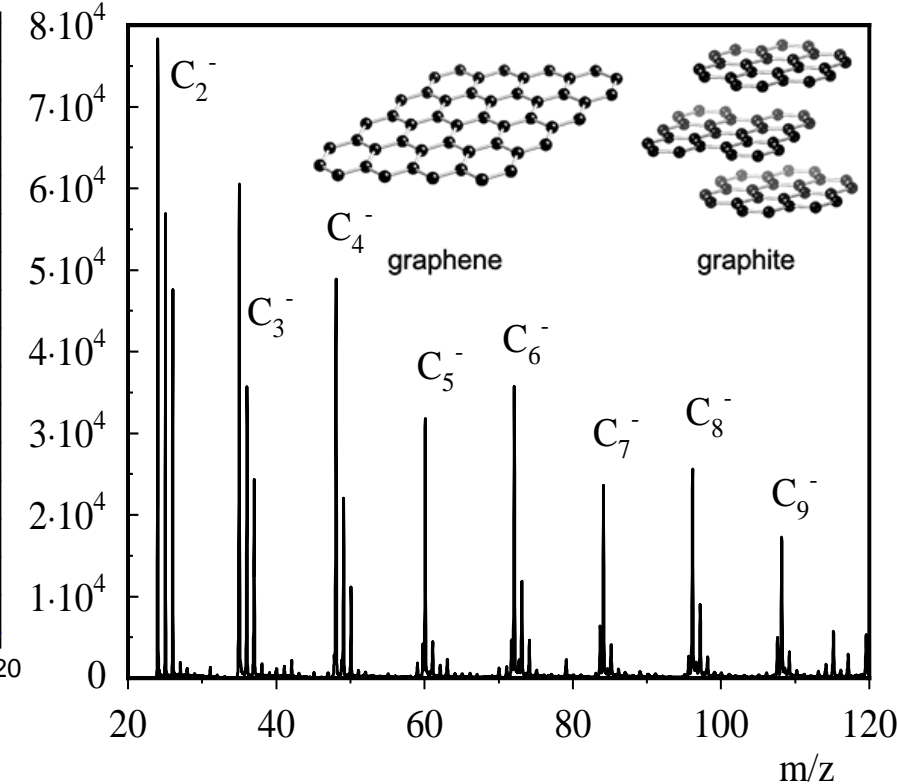


MeV-TOF-SIMS

Carbon on the surface
of a fully conditioned Cu



Graphene reference sample



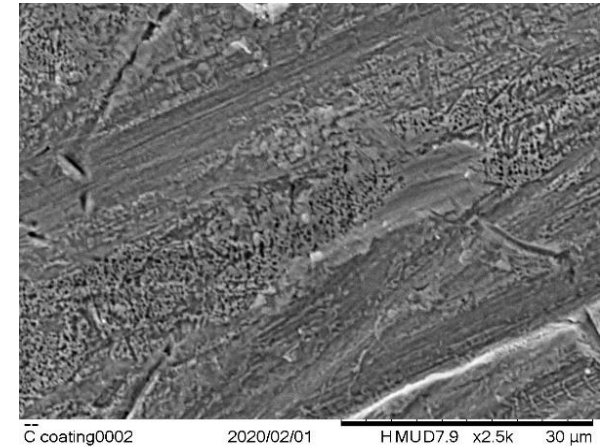
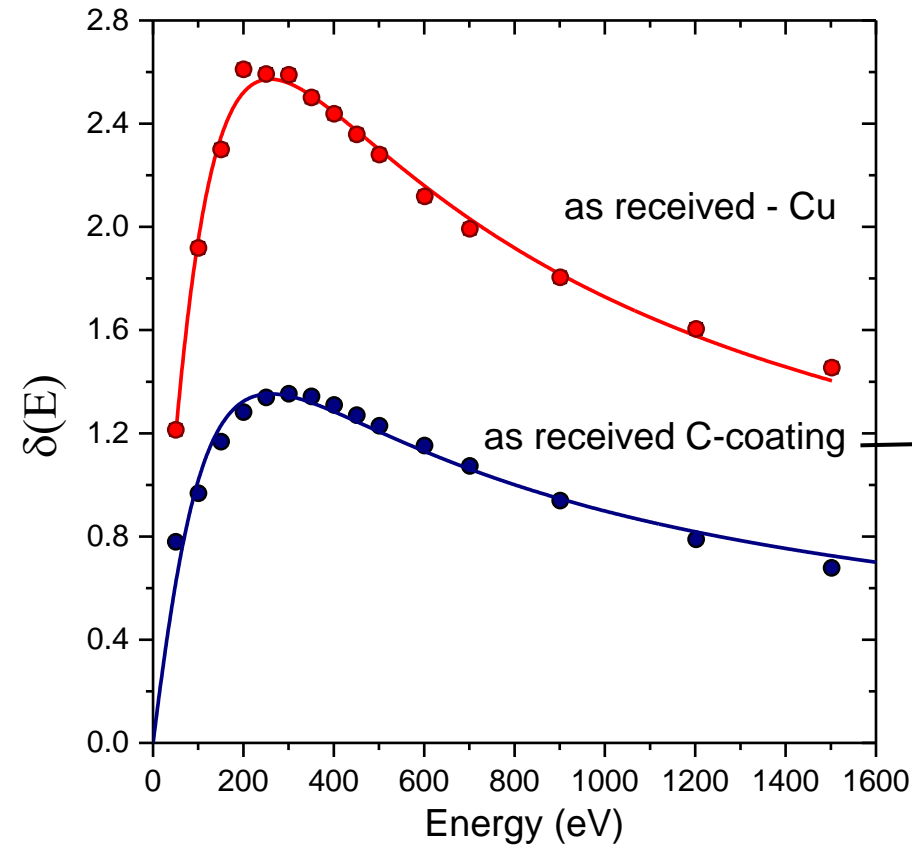
XPS : Modification of the C hybridization : from C-C bonds (sp³) to C=C bonds (sp²) compatible with a graphite structure.

TOF-SIMS : a graphitic (graphene) carbon layer is formed on the surface of the fully conditioned sample (with a large amount of H).

→ Carbon from organic compounds initially present on the surface is transformed into a graphite layer (0.5 nm) by e- irradiation.



Why does the presence of a carbon layer reduces the Cu-SEY?



SEM image of C-coating

→ SEY of carbon is intrinsically lower than the one of copper

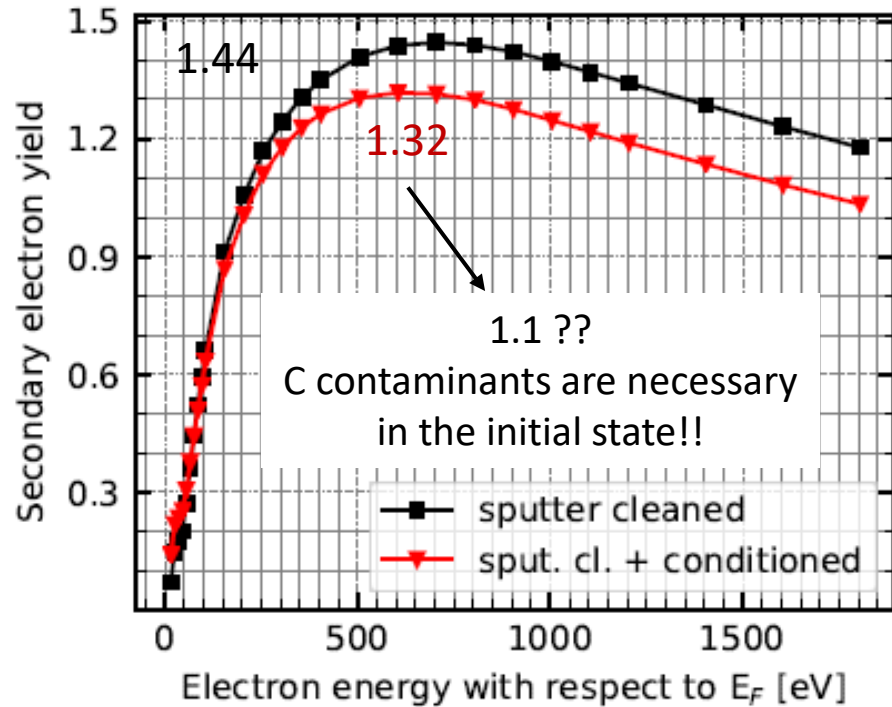
→ Carbon thin film deposited on Cu beam pipe walls is a solution to mitigate the electron cloud build up in the LHC
[P. Pinto Costa, IPAC2014]



Influence of carbon vs removal of contaminants on SEY

Valentine Petit PhD Thesis (CERN 2020)

pure Cu (cleaned, without pollutants)



The conditioning of a sputter-cleaned copper sample results in a δ_{\max} decrease from 1.44 to 1.32 and only a small amount of carbon is observed on the surface after conditioning

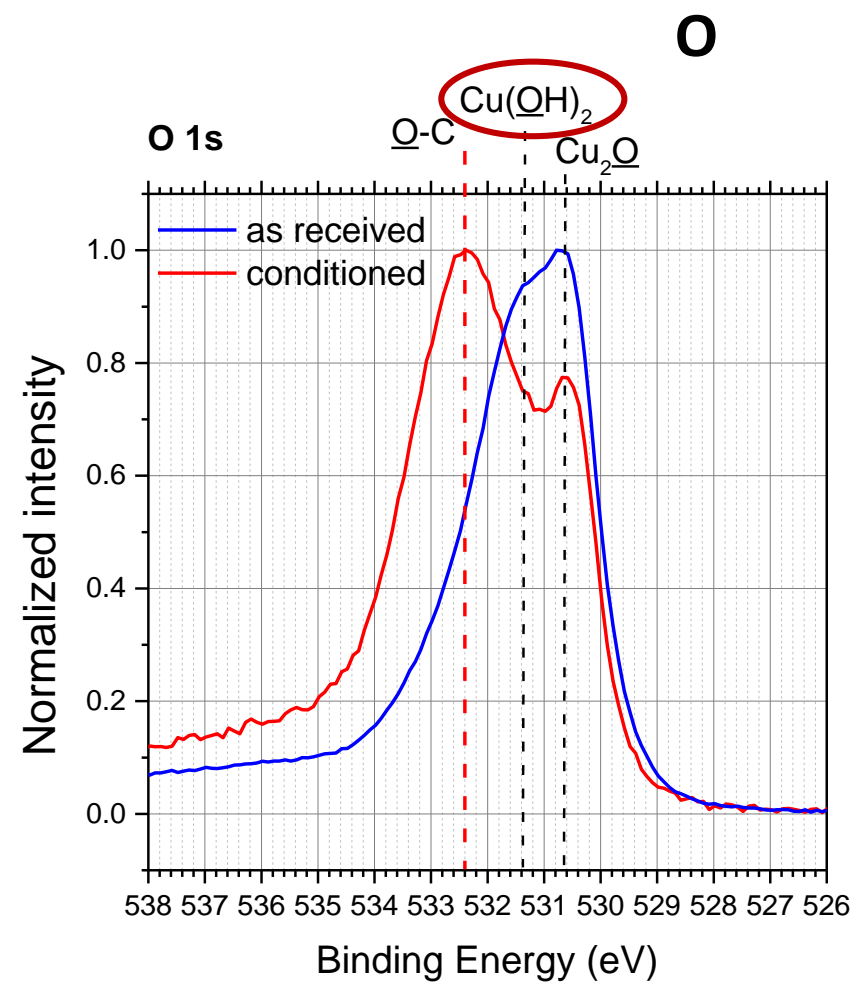
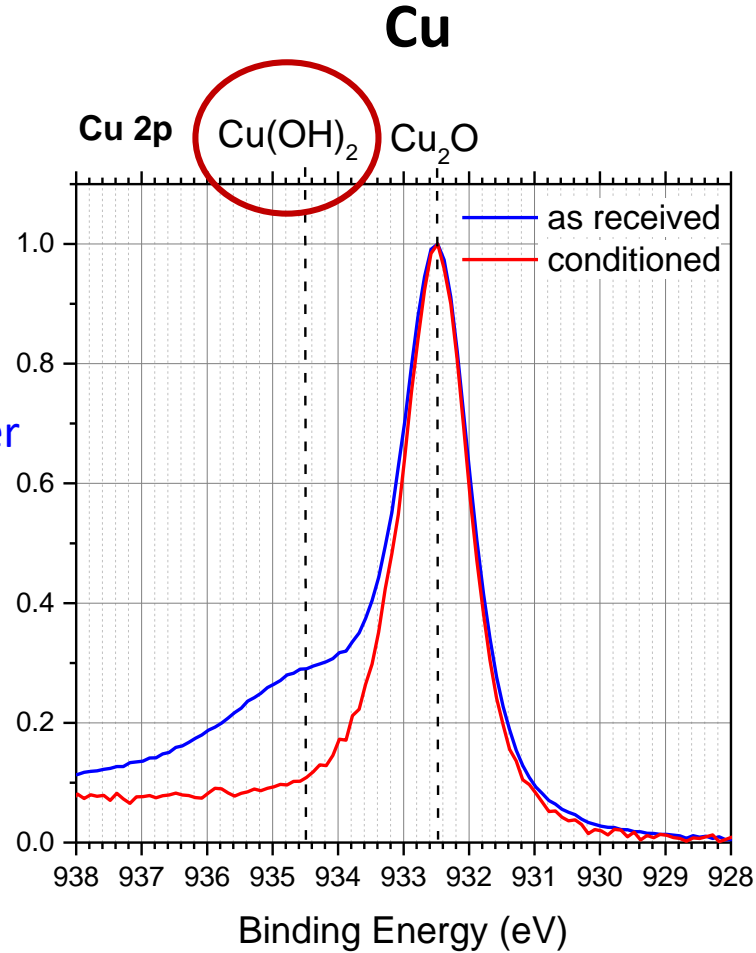
The ultimate δ_{\max} of the cleaned sample after conditioning (1.32) remains still much higher than the one obtained for the conditioning of an air exposed sample (1.1).

The formation of graphitic carbon appears to be necessary to decrease δ_{\max} down to the ultimate value observed on an as received sample



Cu oxide evolution?

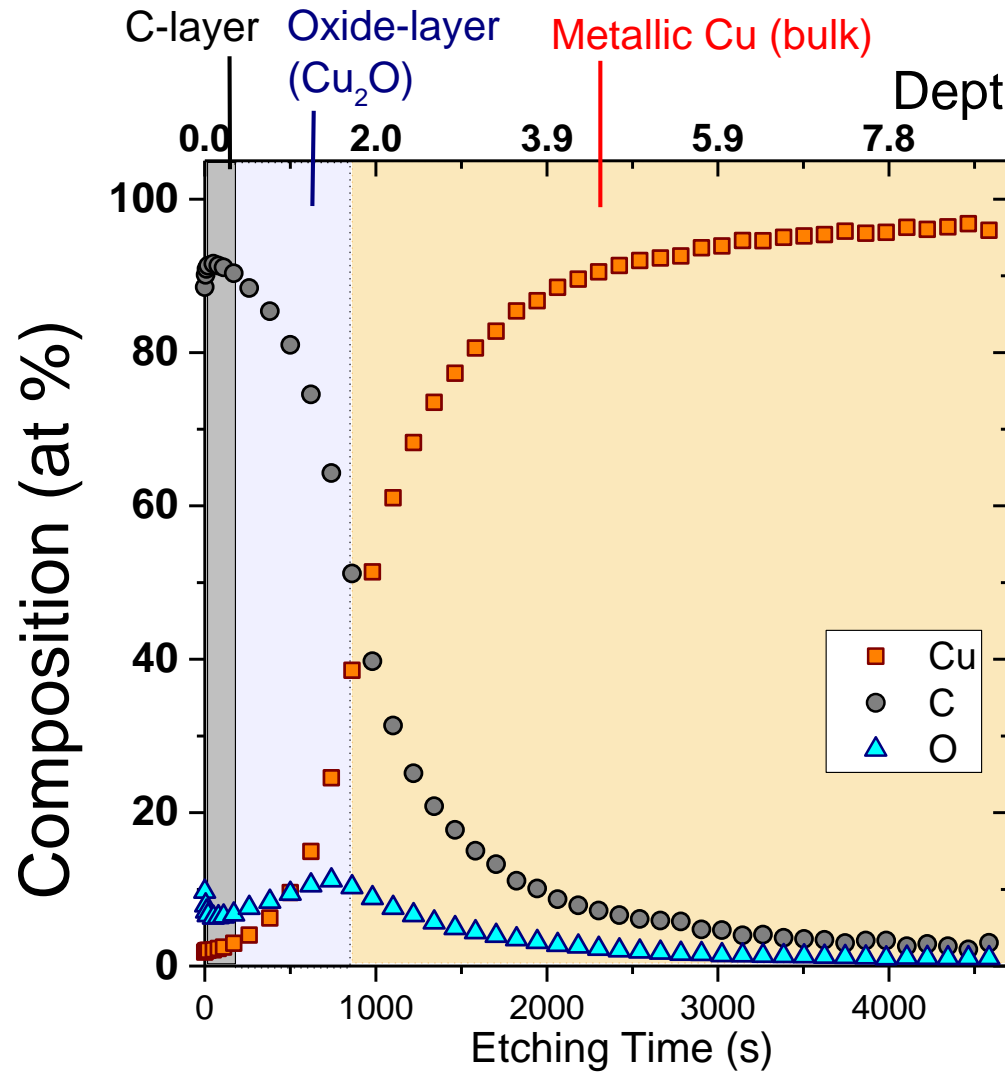
The native oxide layer
 $\text{Cu}_2\text{O} + \text{Cu}(\text{OH})_2$



Modification of Copper oxides after electron bombardment: Cu hydroxide \searrow



Depth profiles of elements in a fully conditioned Cu by XPS analysis

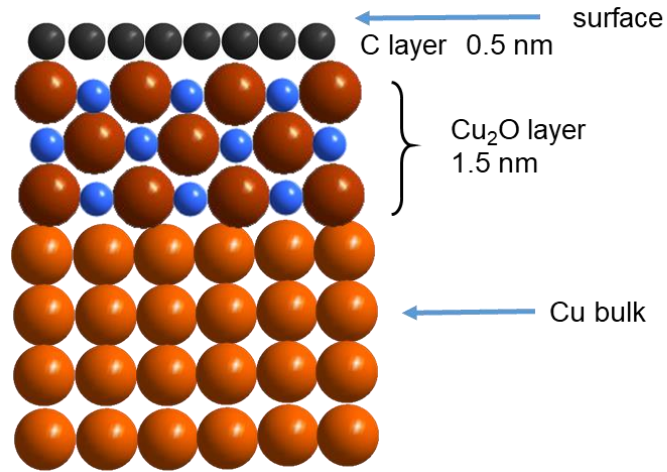


- 1) A graphitic carbon layer is first detected at the extreme surface. The graphitic C layer contains O and H of ≈ 0.5 nm thick.
- 2) At a larger depth, the oxide layer (Cu₂O) is observed of ≈ 1.4 nm thick.
- 3) The copper oxide disappeared and the metallic Cu is detected at a depth larger than 2 nm, and finally metallic Cu is present.

→ Does the presence of the oxide layer influence the SEY of Cu?

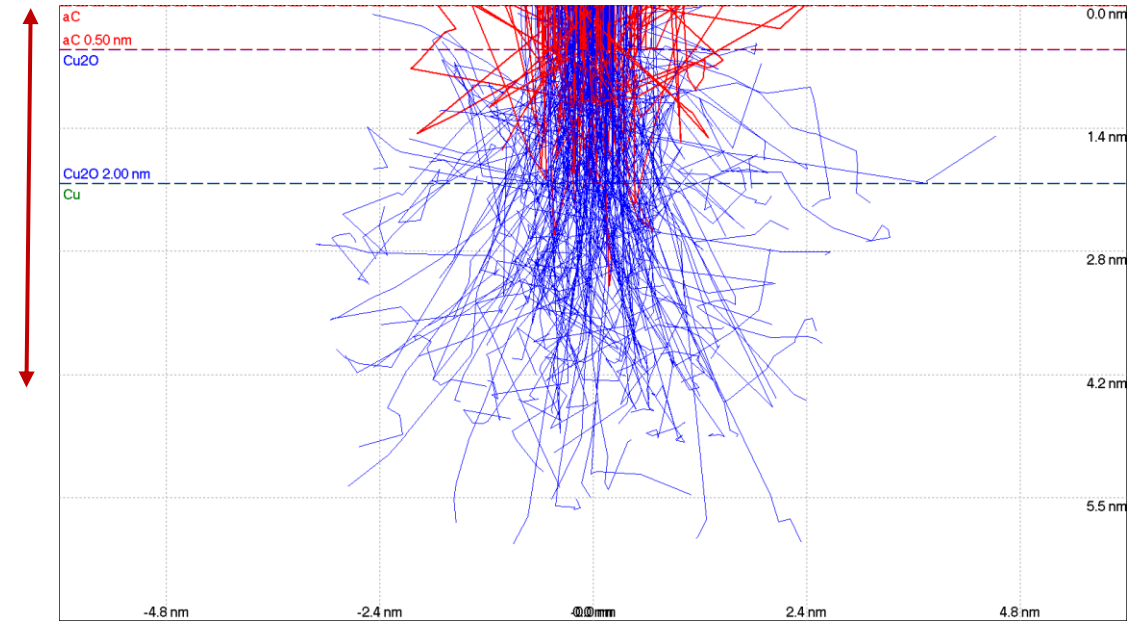


The SEY : contribution of the extreme surface

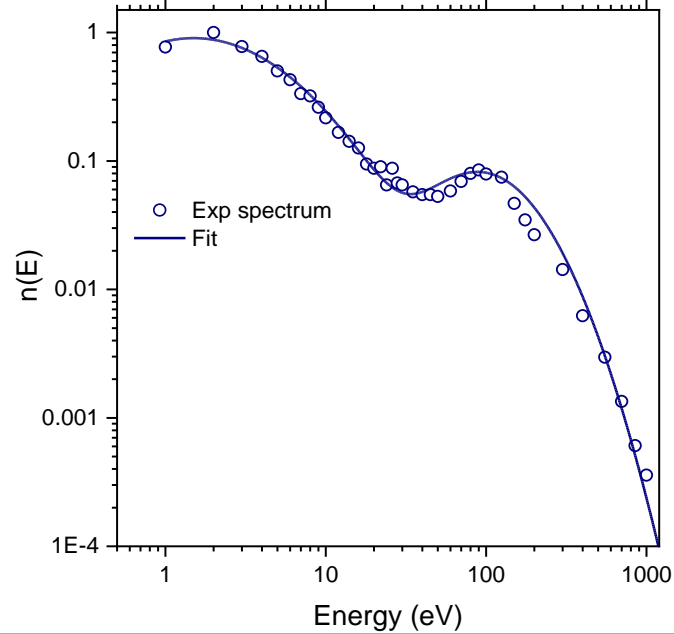


$\approx 4 \text{ nm}$

Penetration depth of 500 eV-electrons

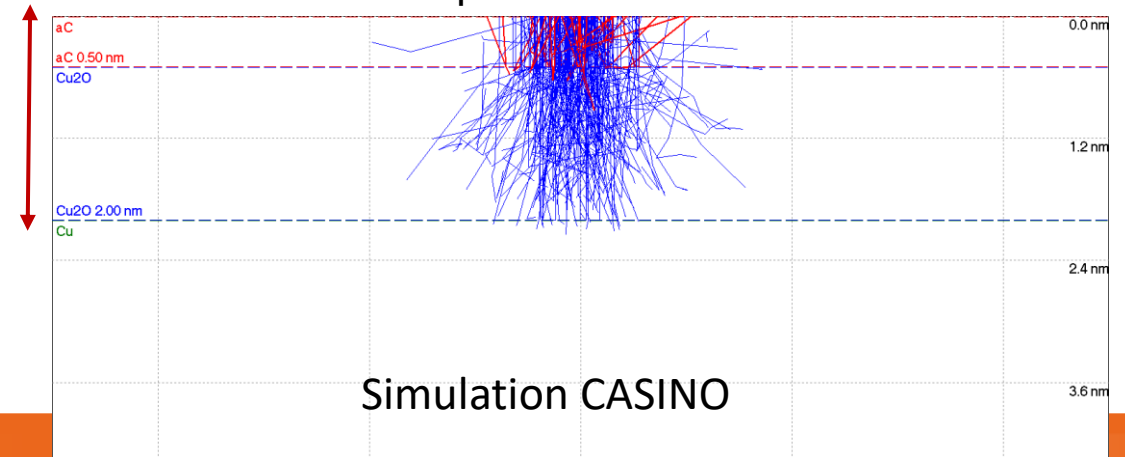


Distribution en énergie des électrons dans le VPS du LHC



$\approx 2 \text{ nm}$

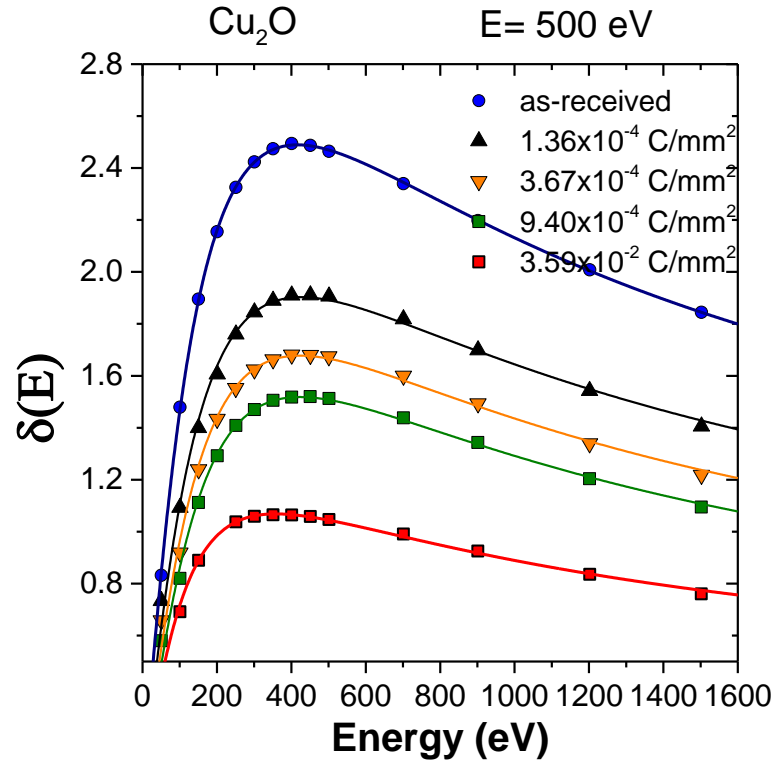
Penetration depth of 200 eV-electrons



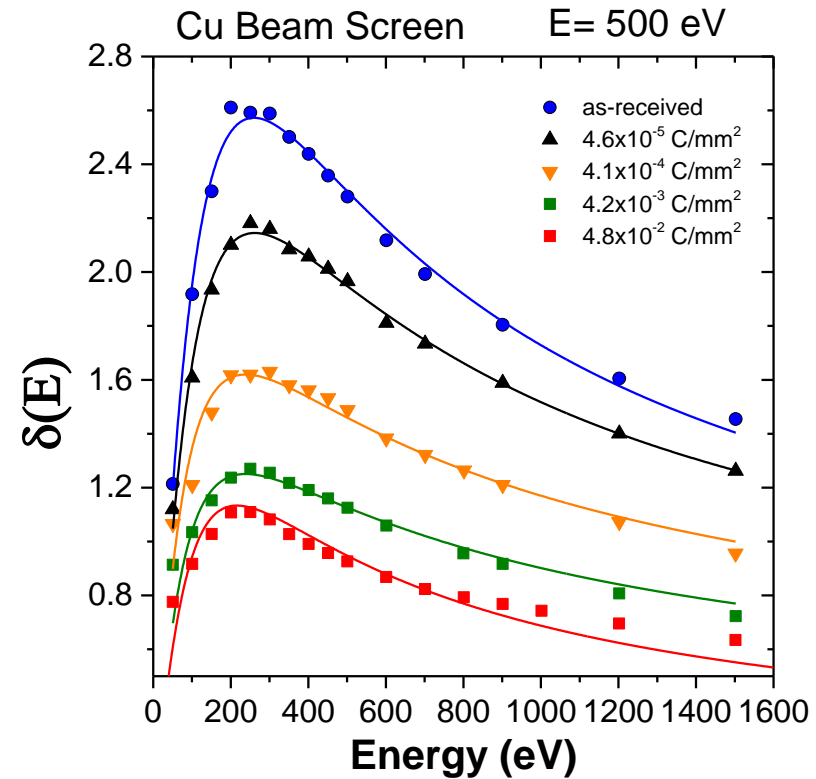


Influence of the Cu oxide layer on SEY?

Pure Cu₂O



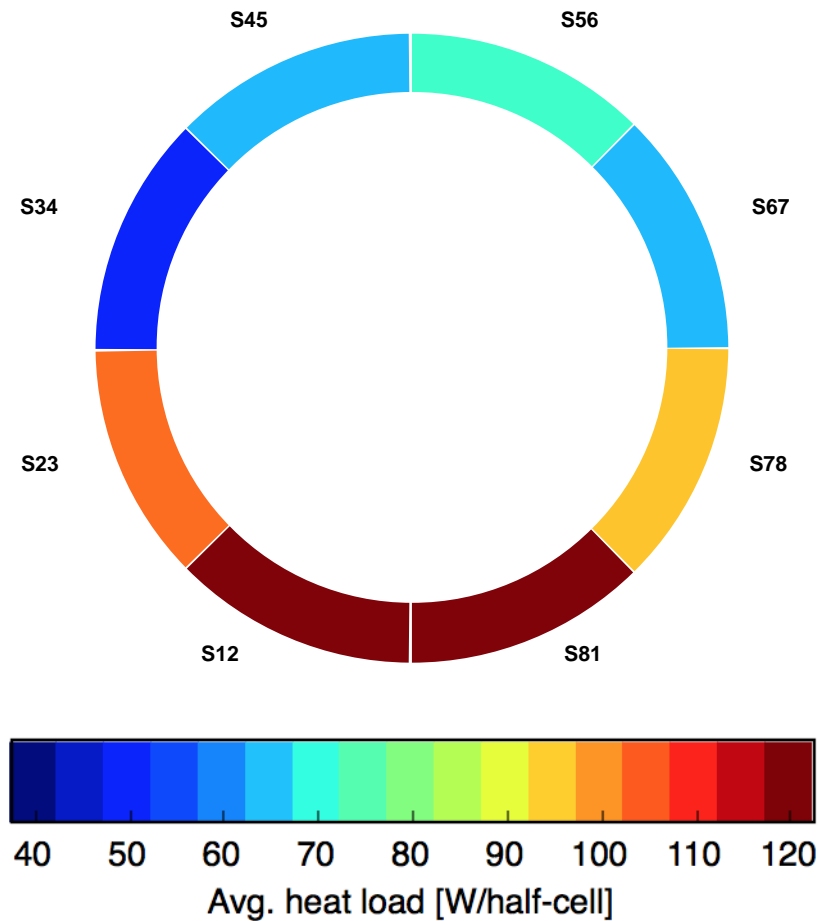
Cu Beam screen



- The SEY curve for Cu₂O has a different shape as the one of Cu Beam screen
- Cu₂O oxide can be conditioned by e- irradiation



Heat load from the e-cloud in the LHC



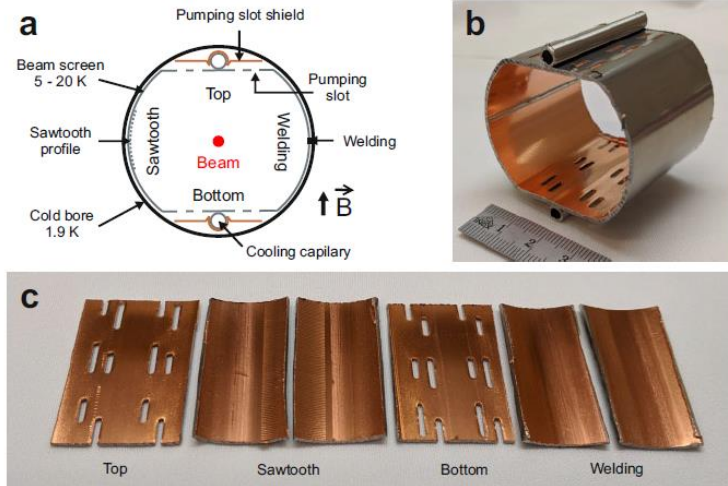
Giovanni Iadarola, CERN
E-CLOUD workshop 2018

- heat load is inhomogeneous along the ring
- machine appears to be splitted into two parts: arcs 34, 45, 56 and 67 have an average heat load lower than for arcs 12, 23, 78 and 81



Why is the E-cloud more intense in some parts of the LHC ?

Valentine Petit PhD Thesis (CERN, 2020) / V. Petit COMMUNICATIONS PHYSICS | <https://doi.org/10.1038/s42005-021-00698-x>

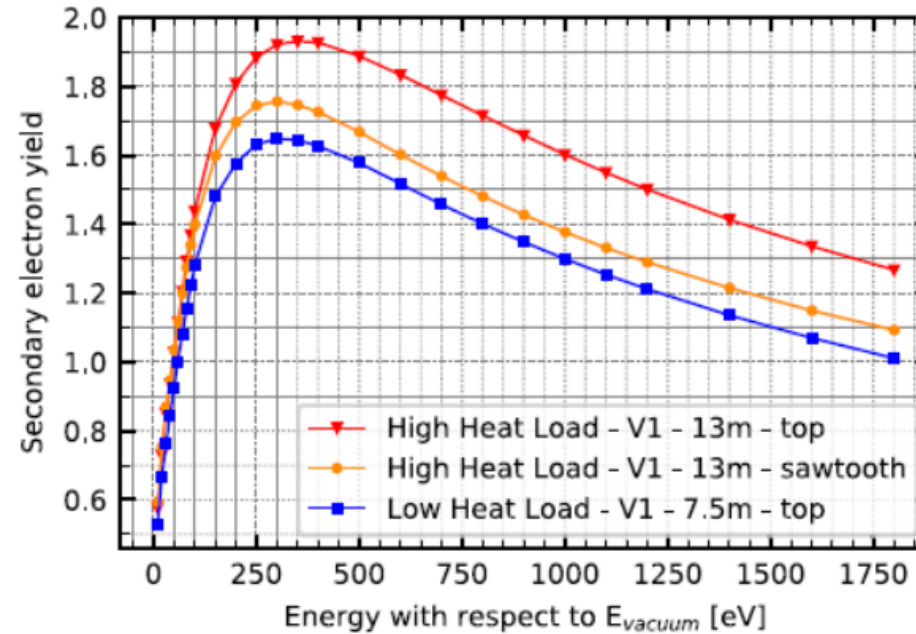
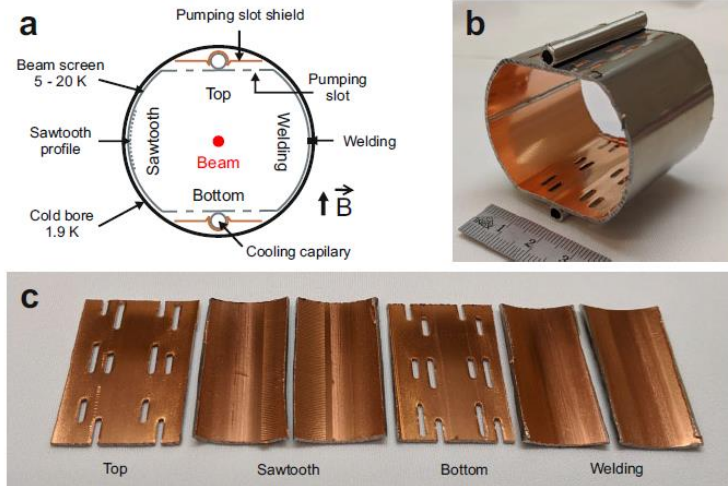


- Beam screen extracted from the LHC beam pipe



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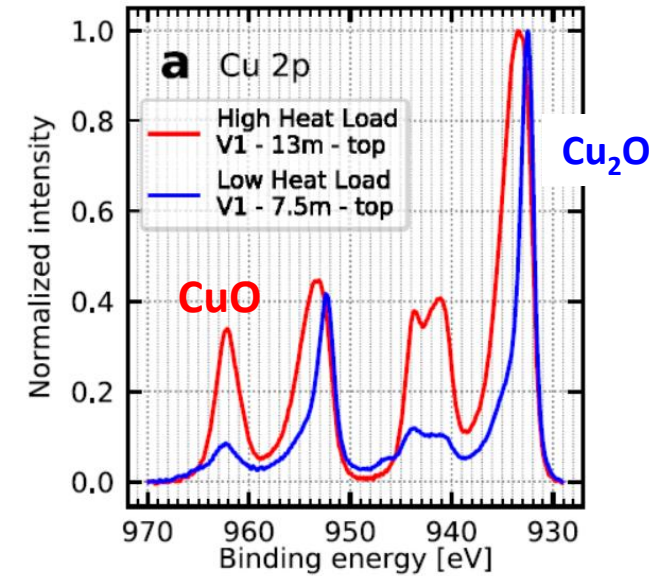
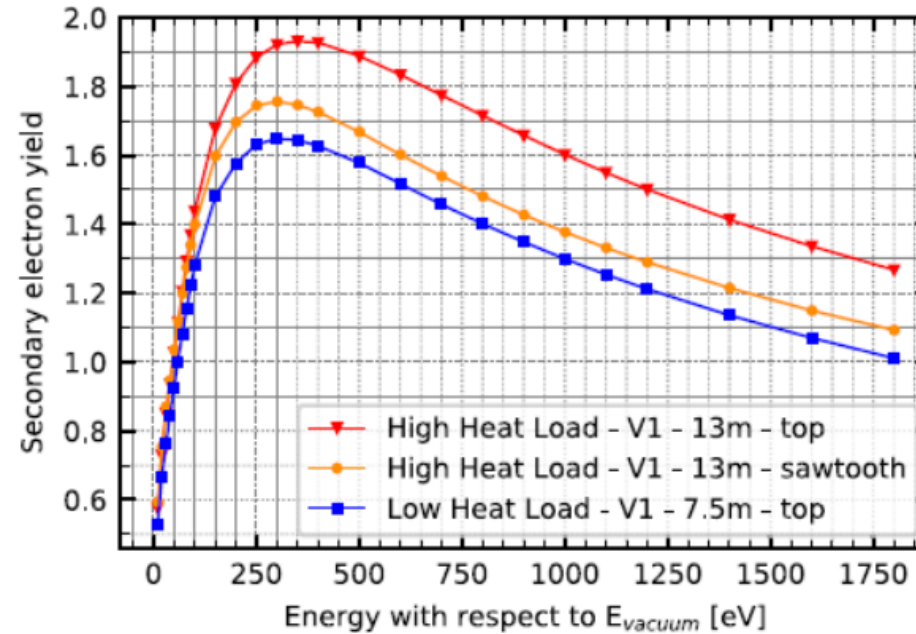
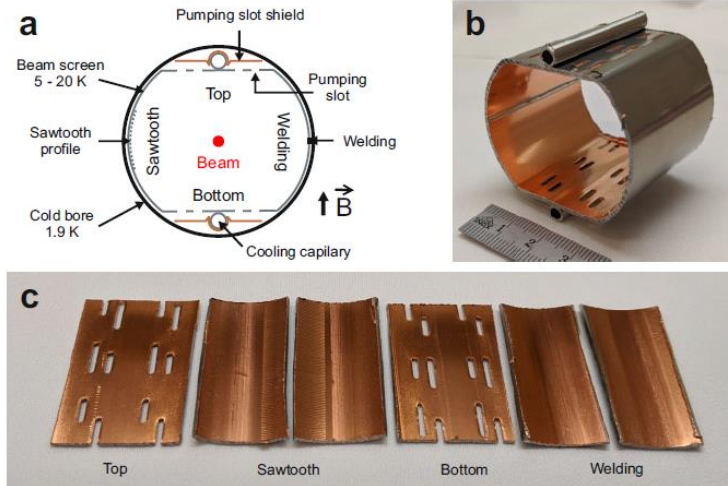


- Beam screen extracted from the LHC beam pipe
- High Heat Load parts exhibit a higher SEY than the Low Load parts



Why is the E-cloud more intense in some parts of the LHC ?

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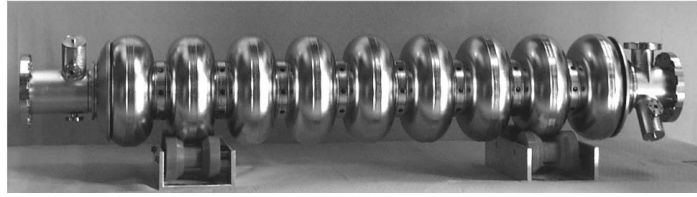
- Beam screen extracted from the LHC beam pipe
- High Heat Load parts exhibit a higher SEY than the Low Load parts
- **CuO was detected (and not the native oxide Cu₂O) in High Heat Load parts !**

**CuO is responsible for the higher SEY observed on this sample (responsible for the high heat loads measured in some arcs)
Where does CuO come from??**

The influence of copper oxides on the conditioning is an important issue for the LHC

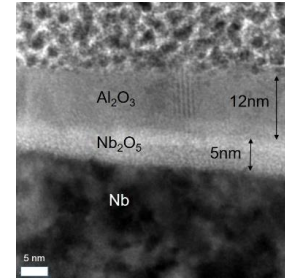
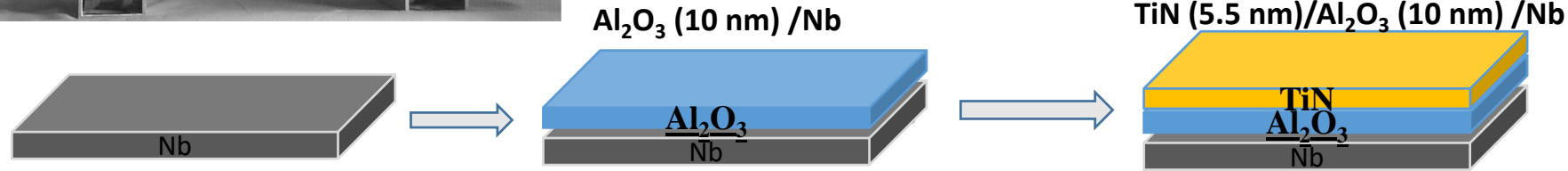


Influence de la nature de dépôts ALD sur le SEY du « Nb »

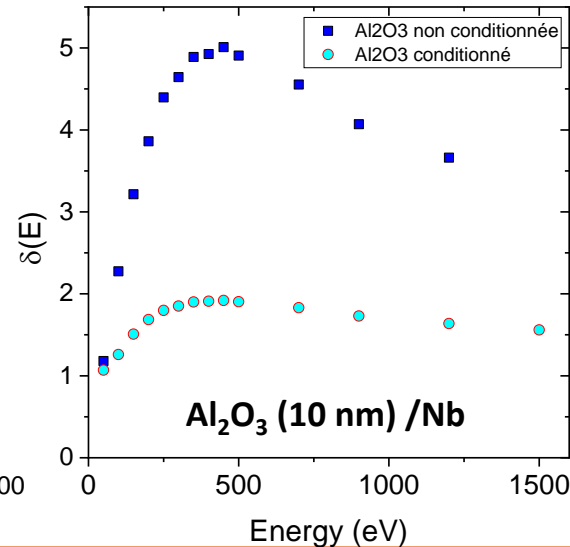
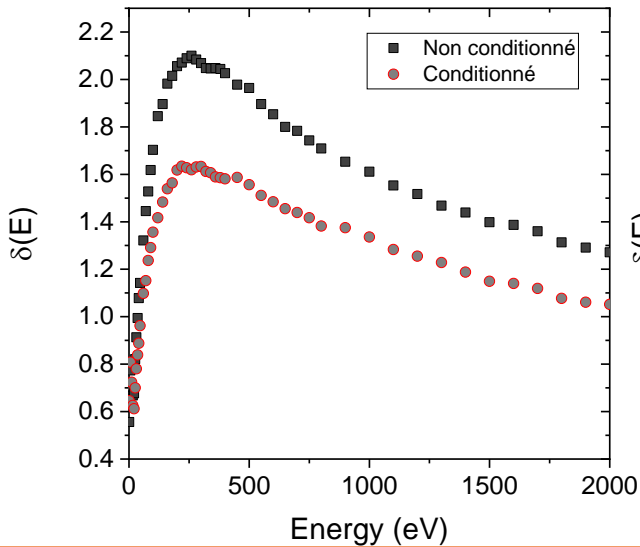


Thèse Sarra Bira (IJCLab)

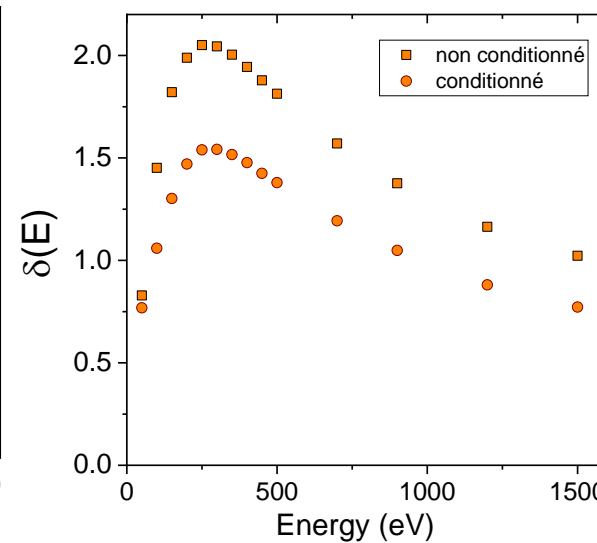
Collab. Dépôts ALD Thomas Proslie / Yasmine Kalboussi



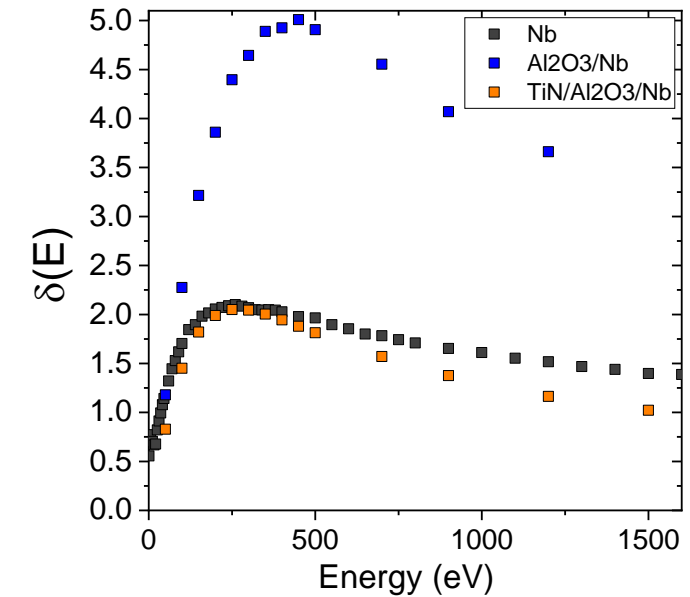
Nb



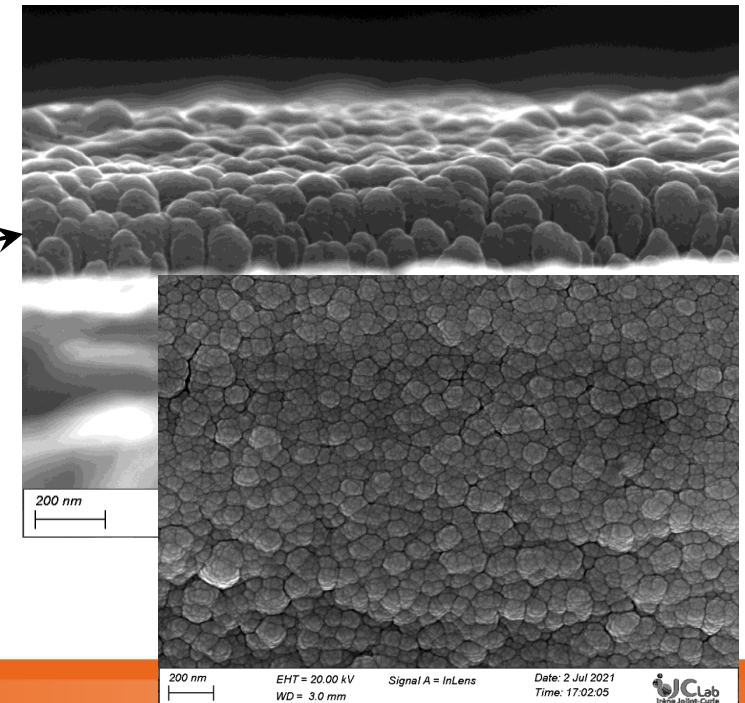
TiN (5.5 nm)/Al₂O₃ (10 nm) / Nb



Comparaison SEY
Matériaux non conditionnés



- **Importance des analyses de surface pour comprendre la relation entre la chimie de surface et :**
 - (i) *la pression dynamique dans les accélérateurs (conditionnement)*
 - (ii) *le processus d'émission d'électrons secondaires (multipacting dans les cavités SRF et lignes de faisceau)*
- Une modification sur quelques nm de profondeur peut avoir des conséquences extrêmement importantes sur les propriétés de surface
- Il est important de développer des bâtis d'analyses en laboratoire adaptés pour répondre à ces problématiques
- **Perspectives R&D:**
 - (i) Influence de l'épaisseur de dépôt (dépôt C) + rôle de CuO sur le SEY du Cu (LHC)
 - (ii) Nature/épaisseur de dépôts ALD : études exploratoires pour identifier d'autres matériaux antimultipacting que TiN (nitrures métalliques ou carbure): thèse en collaboration avec le SIMAP/LPSC (Grenoble)
 - (iii) Influence de l'épaisseur et la microstructure de **dépôts NEG** sur son efficacité (pompage distribué et antimultipacting/WP Vacuum pour FCC-ee)
 - (iv) Acquisition de bâtis d'analyses multitechniques (EQUIPEX PACIFICS) pour renforcer les équipements de la plateforme Vide&Surfaces de IJCLab





Thanks for your attention

